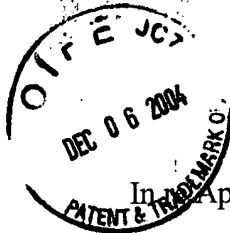


IFW



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor/Applicant:

Wang Yueh et al.

Serial No.: 10/761,842

Filed: January 21, 2004

For: Reducing Outgassing of Reactive
Material Upon Exposure of
Photolithography Resists

§
§
§
§
§
§
§
§
§

Art Unit: 1752

Examiner: Sin J. Lee

Docket: ITL.1058US
P17800

Mail Stop **Amendment**
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

REPLY TO PAPER NO. 10012004

Sir:

In response to the office action mailed October 5, 2004, please amend the above-referenced patent application as follows:

Date of Deposit: December 2, 2004
I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.
Cynthia L. Hayden
Cynthia L. Hayden